

CJM  
9-27-00# 7/B  
36-07IN THE UNITED STATES PATENT AND TRADEMARK OFFICE *Harrison*

Application Serial No. 09/388,826  
Filing Date September 1, 1999  
Inventor Weimin Li et al.  
Assignee Micron Technology, Inc.  
Group Art Unit 2813  
Examiner E. Kielin  
Attorney's Docket No. MI22-1208  
Title: Low k Interlevel Dielectric Layer Fabrication Methods

RESPONSE TO JULY 25, 2000 OFFICE ACTION

To: Box Non-Fee Amendment  
Assistant Commissioner for Patents  
Washington, D.C. 20231

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Responsive to the Office Action dated July 25, 2000, Applicant amends and remarks as follows [unless otherwise indicated, deletions are bracketed, additions are underlined]:

AMENDMENTSIn the Specification:

Page 2, line ~~15~~, change the previously amended language "at an exemplary" to --and at an exemplary--.

Page 12, line ~~4~~, change "a whole of all" to --the whole or all--.